

CLAIMS

1. A processing liquid coating apparatus for coating
a surface of a substrate with a processing liquid, said
5 apparatus comprising:

a substrate holder for holding and rotating the substrate;
and

a processing liquid supply unit disposed apart from the
substrate held by said substrate holder;

10 wherein said processing liquid supply unit has a
plurality of supply ports for supplying the processing liquid
to a plurality of portions including a central portion of
the surface of the substrate, and the processing liquid is
a resist liquid or a developer.

15

2. A processing liquid coating apparatus according to
claim 1, wherein said processing liquid supply unit has a
plurality of suction ports for sucking the processing liquid
on the substrate.

20

3. A processing liquid coating apparatus according to
claim 2, wherein said plurality of supply ports and said
plurality of suction ports are arranged alternately and
linearly.

25

4. A processing liquid coating apparatus according to
claim 1, wherein said processing liquid supply unit is movable
in a radial direction of the substrate.

30

5. A processing liquid coating apparatus according to
any one of claims 1 to 4, further comprising a processing
liquid suction unit for sucking the processing liquid from
a peripheral portion of the substrate.

6. A processing liquid coating apparatus according to any one of claims 1 to 5, further comprising a gas supply unit for ejecting a gas toward the surface of the substrate, said gas supply unit being movable from the central portion to a peripheral portion of the substrate.

7. A processing liquid coating method for coating a surface of a substrate with a processing liquid, said method comprising:

rotating the substrate; and

supplying the processing liquid to a plurality of portions including a central portion of the surface of the substrate;

wherein the processing liquid is a resist liquid or a developer.

8. A processing liquid coating method according to claim 7, further comprising sucking the processing liquid from a plurality of portions of the surface of the substrate.

9. A processing liquid coating method according to claim 7, further comprising sucking the processing liquid from a plurality of portions including a peripheral portion of the surface of the substrate.

10. A processing liquid coating method according to any one of claims 7 to 9, further comprising:

ejecting a gas from a gas supply unit toward the surface of the substrate; and

moving said gas supply unit from the central portion to a peripheral portion of the substrate.